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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
Masahiro SHIRATORI et al.) Confirmation No.: 2482
Application No.: 10/777,213) Group Art Unit: 1763
Filed: February 13, 2004) Examiner: Allan W. Olsen
For: ETCHING MASK)

Commissioner for Patents
U.S. Patent and Trademark Office
Alexandria, VA 22314

Sir:

RESPONSE TO RESTRICTION REQUIREMENT

In response to the Restriction Requirement dated March 17, 2006, the period for response to which extends through April 17, 2006, Applicants hereby elect the invention identified in the Office Action as "Group I, Claims 1-6."

Applicants respectfully request formal examination of this application.

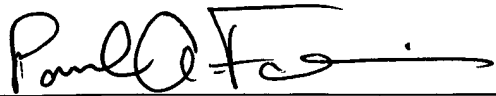
Applicants respectfully assert that no fee is due in connection with the filing of this response. However, if there are any fees due in connection with the filing of this response, please charge those fees to Deposit Account No. 50-0573.

Respectfully submitted,

DRINKER BIDDLE & REATH LLP

Dated: April 13, 2006

By:


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